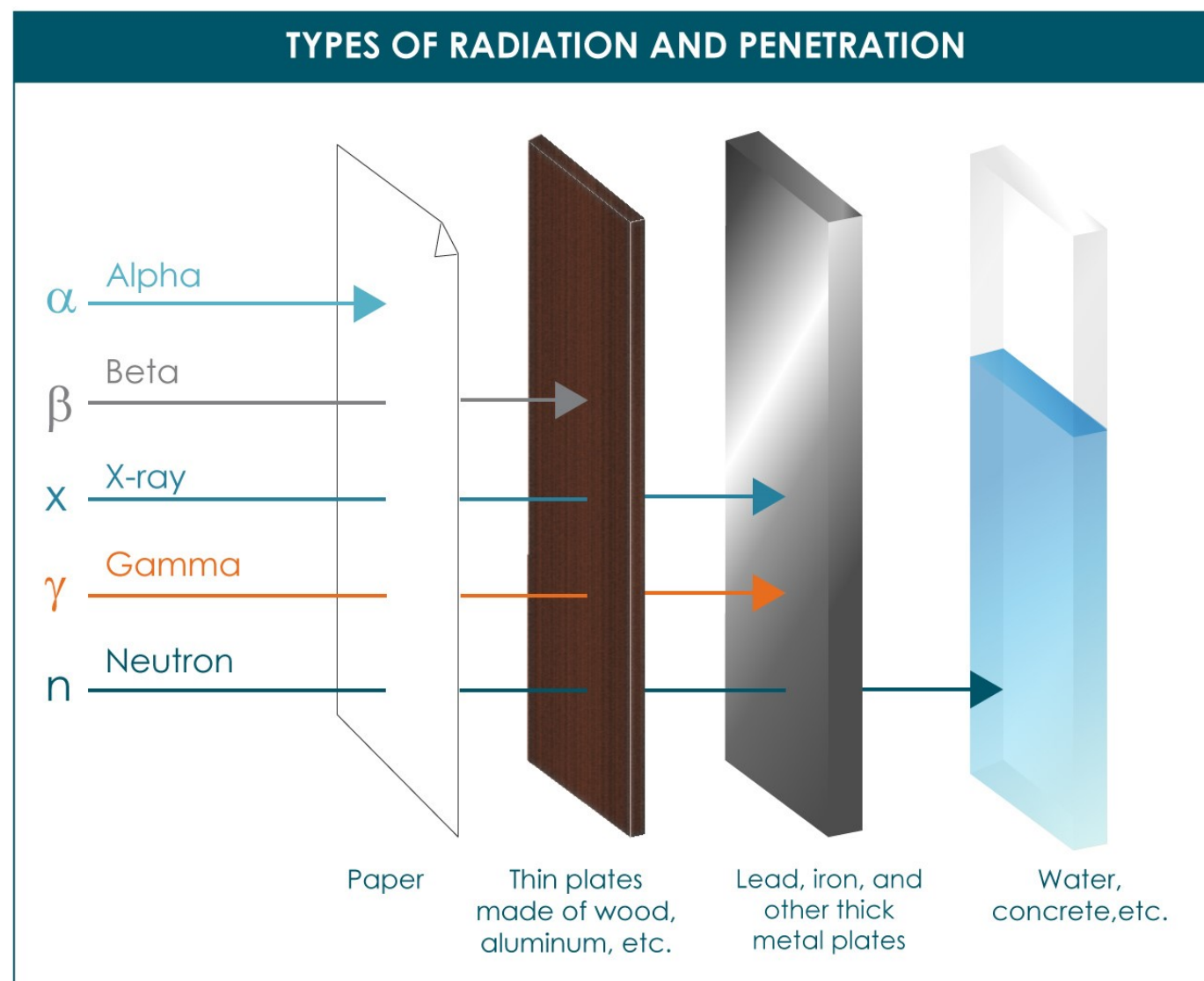


# Effects of ionizing radiation in semiconductor devices: simulation with *Geant4*

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**Goal of this work** to analyze and simulate the effects of ionizing radiation on silicon-based integrated circuits.



When ionizing radiations collide with a semiconductor, they create electron-hole pairs:


- $\alpha$  and  $\beta$  particles progressively lose their kinetic energy when crossing the material
- $\gamma$  rays pass through or are absorbed (photoelectric, Compton effect or  $e^+e^-$  pair production)
  - secondary charged particles if absorbed
- neutron particles interact with nuclei either elastically or inelastically → Si atoms recoil or secondary particles

Depending on the nature and energy of the ionizing radiations, their stopping power in matter is different. From least to most penetrating: alpha, beta, gamma and neutron.

<https://v2.mirion.com/introduction-to-radiation-safety/types-of-ionizing-radiation/>

## Simulations

**Aim:** determination of the charge (number of deposited electron-hole pairs) in a block of silicon by ionizing radiations.

**Tool:**  software Geant4 (for Geometry and Tracking) developed by CERN

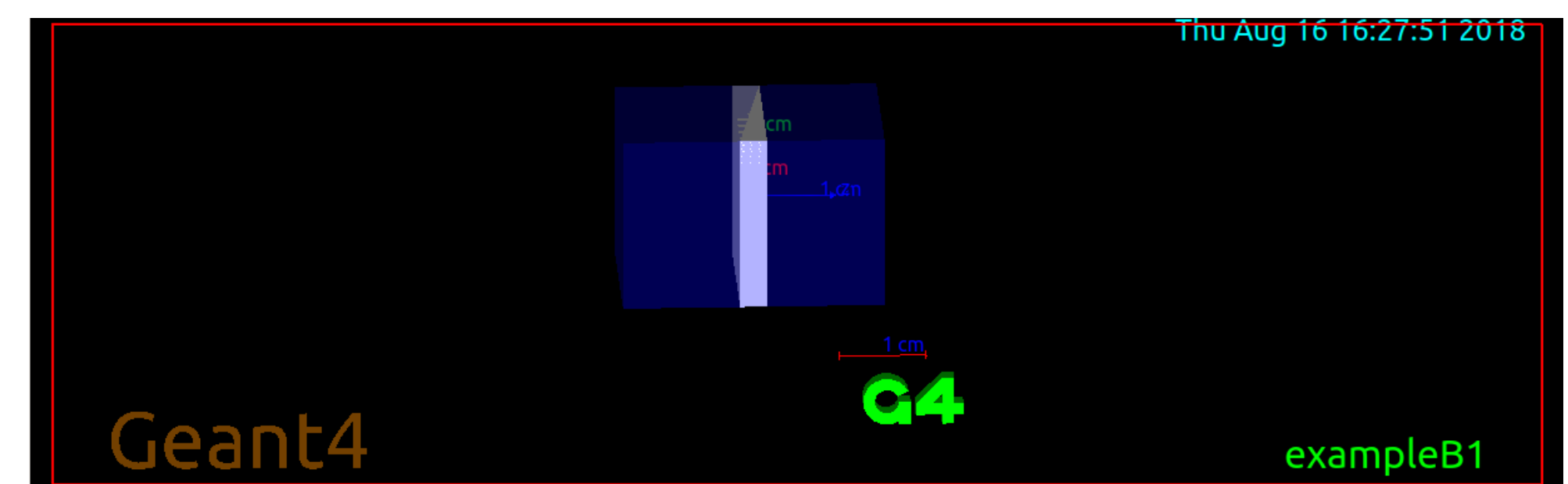
output = absorbed dose value & tracking visualization

platform for the simulation of the passage of radiations through matter, using Monte Carlo methods [1]

**Our work:** implementation of a block of silicon of variable width ( $2 \times 2 \times z \text{ cm}^3$ ) inside an air envelope ( $2 \times 2 \times 3 \text{ cm}^3$ ).

### Studied parameters

- block's thickness
- incident radiations' properties including:
  - type (alpha...),
  - number of particles, and
  - energy.

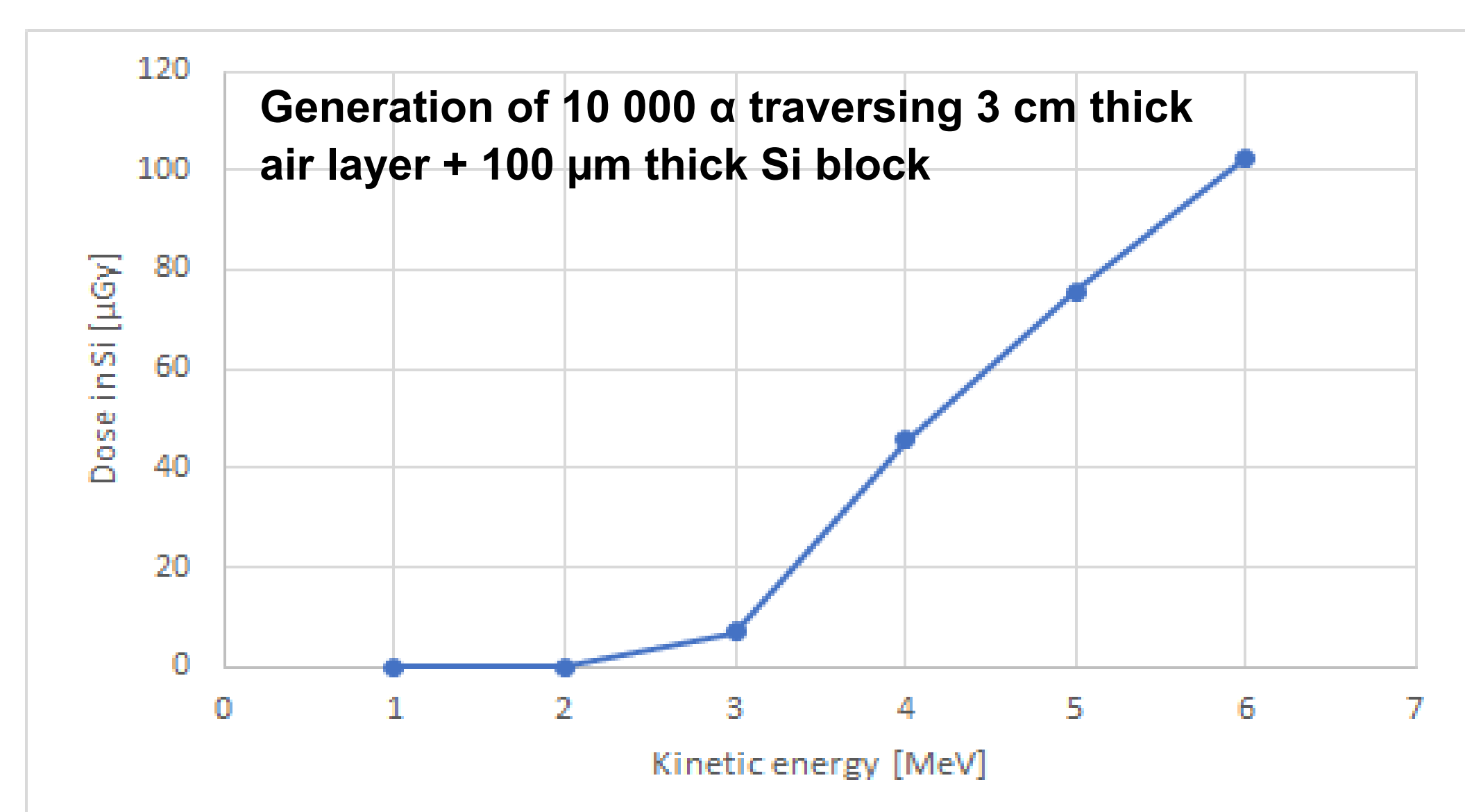
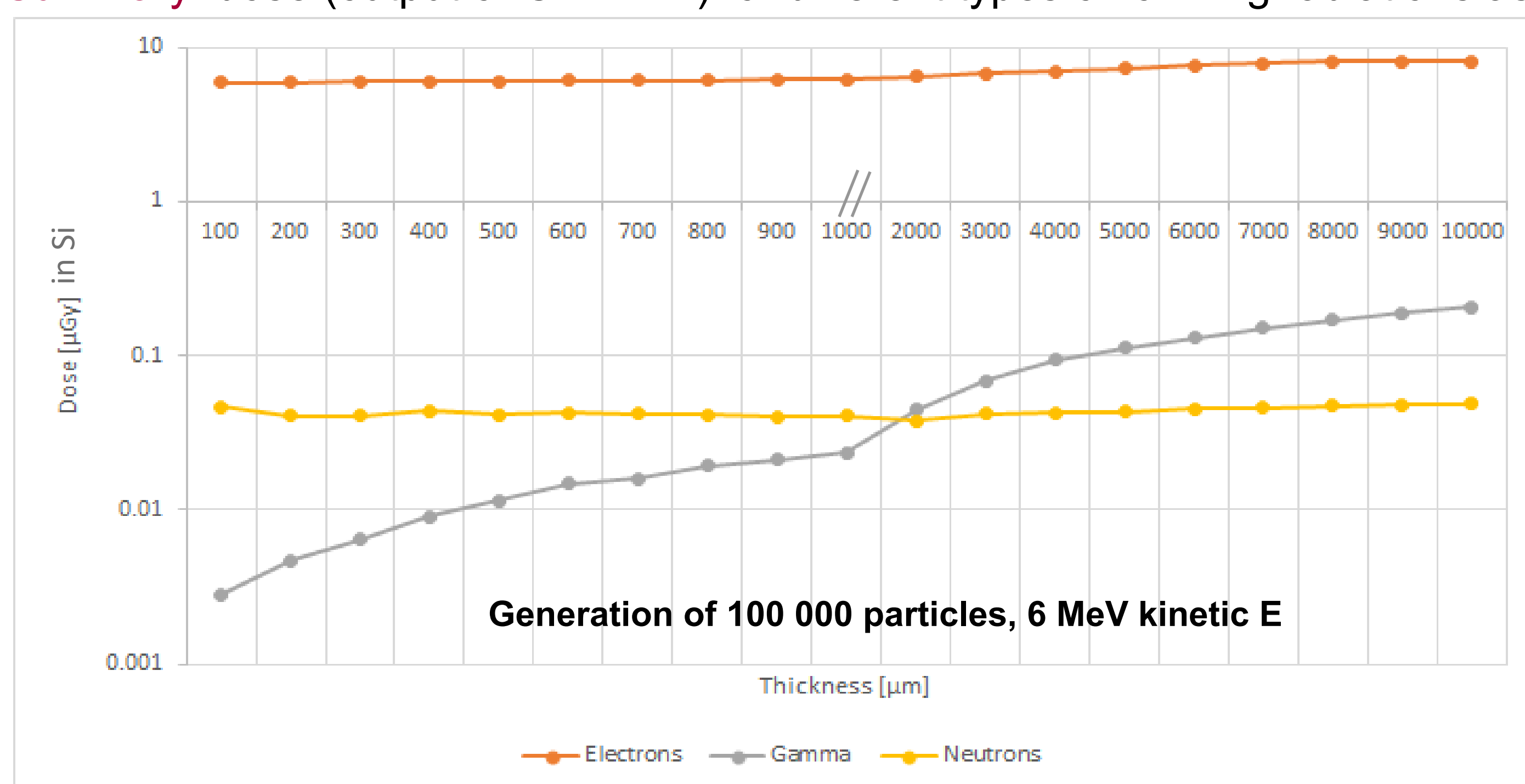


Visualisation of the silicon block on Geant4

For integrated circuits fabrication, the silicon is doped. Nevertheless, considering the low concentration of dopants (typically maximum  $10^{18}$  atoms/cm<sup>3</sup> of dopants for approximately  $10^{22}$  atoms/cm<sup>3</sup> in intrinsic crystalline silicon), simulating a block of pure silicon is a good approximation.

## Results

**Summary:** dose (output of GEANT4) for different types of ionizing radiations as a function of silicon thickness or kinetic energy.



### Comments:

- electrons lose their kinetic energy gradually with a longer range compared to  $\alpha$  → the dose slowly increases with thickness
- fast MeV neutrons interact mainly by nuclear elastic scattering processes
  - ionizing energy deposition due to recoil Si atoms
  - few ionization events in Si layer
- $\gamma$  flux decreases exponentially  $N(x) = N_0 e^{-\mu x}$ 
  - the number of  $\gamma$  stopped in Si increases with thickness.
- $\alpha$  radiations interact strongly with matter → loss an important part of their energy in a 3 cm thick air layer before reaching the silicon block → fully stopped by 3 cm of air + 100  $\mu\text{m}$  Si.

**Validation:** The dose values obtained as well as their variation vs Si thickness are consistent with the way that the ionizing radiations are expected to interact in a solid silicon layer.

6 MeV radiation → path in Silicon [2][3]  
 $\alpha$  range  $\approx 30 \mu\text{m}$ ,  $\beta$  range  $\approx 1.5 \text{ cm}$ ,  $\gamma$  half-value-layer  $\approx 15 \text{ cm}$

## Conclusion and future work

- neutron radiations: further studies are needed in order to understand the importance of Non-Ionizing Energy Loss events → possible damages in the Si lattice.
- $\beta$  radiations lead to the highest dose in Si. Computation of the deposited charge (number of e-h pairs) from the passage of 100 000 ionizing  $\beta$  radiations of 6 MeV in a 500  $\mu\text{m}$  thick silicon block:
  - $D \approx 8 \mu\text{Gy}$  →  $\Delta Q \approx 0.6 \text{ nC}$
- Further simulation studies: passage of ionizing radiations in doped Si, pn junctions, circuits to evaluate the intensities of transient currents created by charge deposition.

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## References

- [1] <https://geant4.web.cern.ch/>  
 [2] <https://www.nist.gov/pml/stopping-power-range-tables-electrons-protons-and-helium-ions>  
 [3] <https://www.nist.gov/pml/x-ray-mass-attenuation-coefficients>